218E



Micronic receives order for an MMS mask metrology system from a customer in Asia

Täby, Sweden – November 1, 2007 – Micronic Laser Systems AB (OMX Nordic Exchange Stockholm, Nordic list, Mid Cap, Information Technology: MICR), is a leading global supplier of laser pattern generators for photomasks.

Micronic today received an order for an MMS mask metrology system. In connection to this order, the customer has ordered a major upgrade of a previously delivered LRS-system. The agreement also includes an option for an additional LRS-system. The MMS system is scheduled for delivery during 2007.

"We are pleased to see that the development within the display industry continues," said Sven Löfquist, president and CEO of Micronic. "This order is further proof of the industry's confidence in Micronic's total solution. The pattern generator LRS and metrology system MMS form a powerful combination, capable of providing the entire package of capabilities needed for advanced display photomask pattern generation and measurement. We now also note that our customers want to secure deliveries of equipment for a coming expansion, in this case in the form of an option for an LRS-system."

Company contact:

Sven Löfquist President and CEO Tel: +46 8 638 52 00 sven.lofquist@micronic.se

About Micronic Laser Systems AB

Micronic Laser Systems AB is a Swedish high-tech company engaged in the development, manufacture and marketing of a series of extremely accurate laser pattern generators for the production of photomasks. The technology involved is known as microlithography. Micronic's product offering also includes metrology systems for display photomasks. Micronic's systems are used by the world's leading electronics companies in the manufacture of television and computer displays, semiconductor circuits and semiconductor packaging components. Micronic is located in Täby, north of Stockholm and at present has subsidiaries in the United States, Japan, South Korea and Taiwan. Micronic maintains a web site at: http://www.micronic.se